## **TECHNICAL SPEC FOR Track system**

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TEL Clean Track MKVIII with coater and developer module.

The coater is equipped with a dynamic arm dispense system and Entegris HV pump.

The developer is a spray module build to use solvent like cyclopentanone

## **Tool status:**

The tool, inclusive PI and BARC pumps, have been flushed and cleaned with solvent, and dry cleaned with CCA. The solvent lines (Thinner) have been disconnected from the tool, as wel as the electric power supply lines.  Decommissioning was done by trained Litho technicians.
Specific Model:
Wafer size: 6 and 8 inch
Wafer type: Jeida flat and 8 inch nozzle
Wafer flow: offline unit
Number coater/developer modules:
1 coater, 1 developer (Spray develop)
RRC Pumps & kits:
Solvent & developer auto supply systems:
Temperature / Humidity controller:
Configuration/layout of each block:
GEM:
AVG:

HMDS Bubblers:	
Power supply: 208 V, 3 Phase, AC Transformer:	
/intage:	
Missing parts:	
Defected parts:	
Operating system:	

## **Photos to Collect**

- All 4 sides
- Close up of each module (opened up)
- Inside all cabinets
- Chemical cabinets opened up
- Serial plate
- Serial plate of the laser
- Spare parts, manuals (if any)